

Drafts

Pending

Active

- L1: (7259) cmp.clm. or (chemical adj mechanic
- L2: (299) 1 and optical.clm.
- L3: (245) 2 and light
- L4: (177) 3 and (light or radiat\$4 or wavelen
- L5: (61) 4 and ((material or optical\$2 or lay
- L6: (32) 5 and (optical\$2 near (layer\$1 or ma
- L7: (38329) optical\$2 adj3 (layer or material
- L8: (662) 7 and (cmp or (chemical adj mechani
- L9: (601) 8 and (light or radiation or wavele
- L10: (307) 9 and (endpoint or stop\$4)
- L11: (284) 10 and remov\$4
- L12: (203) 11 and optical.clm.
- L13: (102) 12 and (polish\$4.clm. or planariz\$
- L14: (80) 13 and (endpoint or detect\$3)
- L15: (5) 14 and (optical\$3 adj (material or

Failed

Saved

(0) ("(thinadjfilm)nearresistor").PN.

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14 and (optical\$3 adj (material or layer)).clm.

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U	I	P	P	Document ID	Issue Dat	Pages	Title	Current OR	Current XR	Retrieval	Inventor	S	C	3	4	5
				US 20020135778	20020926	11	Fabrication of	356/515			Folta, James A. et al.					
				US 20020037600	20020328	41	Method of manufacturing	438/30	438/57;		Hirabayashi,					
				US 6661025	20031209	40	Method of manufacturing	257/53	438/78		Yukiya					
				B2			electro-optical apparat		257/72;		Hirabayashi,					
				US 6285035	20010904	20	Apparatus for detecting	250/559.22	438/149;		Yukiya					
				B1			an endpoint polishing l		250/559.4		Taravade, Kunal N.					
				US 6074517	20000613	17	Method and apparatus	156/345.13	250/338.1;		Taravade, Kunal N.					
				A			for detecting an endpoi		257/E21.23							

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